

METHOD OF PHOTOCATALYTICALLY MAKING THE SURFACE OF BASE MATERIAL ULTRAHYDROPHILIC, BASE MATERIAL HAVING ULTRAHYDROPHILIC AND PHOTOCATALYTIC SURFACE, AND PROCESS FOR PRODUCING SAID MATERIAL

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Inventor(s): KOJIMA EIICHI (JP); CHIKUNI MAKOTO (JP); FUJISHIMA AKIRA (JP); HAYAKAWA MAKOTO (JP); HASHIMOTO KAZUHITO (JP); KITAMURA ATSUSHI (JP); MACHIDA MITSUYOSHI (JP); NORIMOTO KEIICHIRO (JP); WATANABE TOSHIYA (JP)

Applicant(s): TOTO LTD (JP)

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Cited
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Abstract

A method of making the surface of a base material ultrahydrophilic which comprises the step of coating the surface with a layer containing photocatalytic semiconductor material such as titania and the step of photoexciting the photocatalytic material to adjust the angle of contact of the surface of the above layer with water to about 10 DEG or less. When this method is applied to the surface of a base material such as mirror, lens or windowpane, the growth of waterdrops is prevented and the base material becomes highly antifogging. The articles treated by this method do not undergo any deposition of contaminants on the surfaces thereof and are readily cleaned by rainfall or washing with water. 

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